



# YES-ÉcoClean

## Automated Plasma Photoresist Strip/Descum System

*Powerful, Damage-Free Cleaning Removes Photoresist, Polyimide and BCB*

### Specifications

<b>Hardware</b>	
Clean Room Compatibility	Class 10
Hot Plate Temperature Range	50° to 300 °C
Capacity	Single wafer/2"-200mm/silicon, GaAs, sapphire, ceramic
Pins up/Pins down process mode	Pins up or down for process flexibility
Throughput	≥ 50 wph/ 4μ photoresist/ 250°C process
Process Gas Inputs	2 MFCs standard (Oxygen and Nitrogen), 3 <sup>rd</sup> forming gas MFC optional
Process Chamber Dimensions	33.02 cm (W) x 30.50 cm (D) x 15.24 cm (H) (13" x 12" x 6")
Hot Plate Process Area	49 in <sup>2</sup> maximum (200mm wafer)
Wafer Handling Robot	Single arm, surface-mount design 7.25" Z travel/ 50-200mm wafers Multiple end effectors are available for various substrates and materials
Overall System Dimensions	50.8 cm (W) x 144.4(D) x 171.4 cm (H) (20" x 56.85" x 67.48")
Chamber Material	6061-T6 aluminum
Compliance	SEMI S2, S8
<b>Software</b>	
User Interface	PC with touch screen monitor and pull-out keyboard, barcode reader
Number of Recipes	File-based data collection
SECS/GEM	Optional
<b>Performance</b>	
<b>Descum Specifications</b>	
<ul style="list-style-type: none"> <li>Estimated Throughput</li> </ul>	Up to 65 wph @ 10 second process
<ul style="list-style-type: none"> <li>Approx. Ash Rate</li> </ul>	100-2000Å/ min
<ul style="list-style-type: none"> <li>Uniformity</li> </ul>	Within Wafer: +/- 10% Wafer to Wafer: +/- 10% Lot to Lot: +/- 10%
<b>Photoresist Strip Rate</b>	
<ul style="list-style-type: none"> <li>Strip Rate</li> </ul>	Up to 10 μm/min @250°C
<ul style="list-style-type: none"> <li>Handling Speed</li> </ul>	15-30 sec process= 50-60 wph
<ul style="list-style-type: none"> <li>Uniformity 200 mm (Silicon)</li> </ul>	Within Wafer: +/- 10% Wafer to Wafer: +/- 10% Lot to Lot: +/- 10%
<b>Additional</b>	
Power Requirements	208 VAC 4-wire 3PH, 50/60 Hz, 30 Amps
<ul style="list-style-type: none"> <li>RF Power Supply</li> </ul>	RF Automatic, fully-contained, water-cooled system
<ul style="list-style-type: none"> <li>Requires chilled water</li> </ul>	For chamber and plasma source
<ul style="list-style-type: none"> <li>Requires vacuum pump</li> </ul>	200-350 CFM vacuum pump
Compliance	CE, UL, CSA, Korea



### Contact Us

Please call us to run a process demonstration. Call +1 925-373-8353 (worldwide), 1-888-YES-3637 (US toll free), or visit us online at [www.yieldengineering.com](http://www.yieldengineering.com).

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